We Claim:

1. Lens with at least one aspheric lens surface, wherein, on describing the aspheric lens surface by means of Zernike polynomials, the following holds for the aspheric lens surface:

$$P(h) = \frac{h^2}{R(1 + \sqrt{1 - \frac{h^2}{R^2}})} + K0 + K4 * Z4 + K9 * Z9 + K10 * Z16 + K25 * Z25$$

with

$$Z4 = (2 \times h2 - 1)$$

$$Z9 = (6h4 - 6h2 + 1)$$

$$Z16 = (20h6 - 30h4 + 23h2 - 1)$$

$$Z25 = (70h8 - 140h6 + 90h4 - 20 h2 + 1)$$

$$Z36 = (252h10 - 630h8 + 560h6 - 210h 4 + 30 h2 - 1)$$

$$Z49 = (924h12 - 27.72h10 + h3150h8 - 1680h6 + h420h4 - 42h2 + 1)$$

$$Z64 = (3432h14 - 12012h12 + 16632h110 - h11550h8 + 4200h6 - 756h4 + 56h2 - 1)$$

where P is the sagitta as a function of the normed radial distance h from the optical axis 7:

distance from the optical axis
$$h = \frac{1}{2} \text{ (lens diameter of the aspheric)} = \text{normed radius}$$

$$0 < h \le 1$$

and wherein at least two of the following conditions is fulfilled:

(a)
$$\left| \frac{K16}{K9} \right| < 0.7$$

(b)
$$\left| \frac{K25}{K9} \right| < 0.1$$

(c)
$$\left| \frac{K36}{K9} \right| < 0.02$$

the radius of the aspheric lens surface being fixed so that K4 = 0.

2. Lens with at least one aspheric lens surface according to claim 1, wherein

for (a),
$$\left| \frac{K16}{K9} \right| < 0.6$$
,

and/or for (b),
$$\left| \frac{K25}{K9} \right| < 0.07$$
,

and/or for (c),
$$\left| \frac{K36}{K9} \right| < 0.015$$
.

- 3. Lens according to claim 1, where in the aspheric lens surface fulfills all three conditions (a) through (c).
- 4. Lens, particularly for microlithography, with at least one aspheric lens surface, wherein the aspheric lens surface is described by:

$$P(h) = \frac{h^2}{R(1 + \sqrt{1 - \frac{h^2}{R^2}})} + K0 + K4 * Z4 + K9 * Z9 + K10 * Z16 + K25 * Z25$$

with

$$Z4 = (2 \times h2 - 1)$$

$$Z9 = (6h4 - 6h2 + 1)$$

$$Z16 = (20h6 - 30h4 + 23h2 - 1)$$

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where P is the sagitta as a function of the normed radial distance h from the optical axis 7:

distance from the optical axis
$$h = \frac{1}{2} \text{ (lens diameter of the aspheric)} = \text{normed radius}$$

$$0 < h \le 1$$

and the resulting components, when using the normed radius, do not exceed the following values:

(a) K9 * Z9
$$\leq$$
 300 μ m, and/or

(b)
$$K16 * Z16 \le 10 \,\mu\text{m}$$
, and/or

(c)
$$K25 * Z25 \le 2 \mu m$$
, and/or

(d)
$$Kc * Zc \le 1 \mu m \text{ for all } c > 35.$$

- 5. Lens according to claim 1, wherein the aspheric lens surface (AS1) is provided on a convex lens surface.
- 6. Objective, wherein the objective includes at least one lens according to claim1.
- 7. Projection objective comprising at least a first and a second region, wherein at least one lens with an aspheric lens surface according to claim 1 is arranged in the lens groups up to and including the second convexity.

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- 8. Objective according to claim 7, wherein a lens surface (S2) is arranged adjacent to the aspheric lens surface (AS1) and has a radius different by less than 30% from the radius of the aspheric lens surface (AS1).
- 9. Objective according to claim 7, where in the objective is a microlithography objective.
- 10. Projection exposure device for microlithography, wherein it contains a projection objective according to claim 7.
- 11. Method of producing microstructured components, in which a substrate provided with a photosensitive layer is exposed by means of a mask and a projection exposure device with a lens arrangement which contains at least one lens with an aspheric lens surface according to claim 1.
- 12. Method of generating new objective designs, wherein for all aspheric lens surfaces provided in the design, the lens surfaces are according to claim 1.
- 13. Compensation optics for testing aspheric lenses, said optics containing at least three lenses, having a test diameter between 120 mm and 350 mm, and being isoplanatically corrected, wherein the imaging scale in testing varies by less than 3%, preferably 1%, between the aspheric surface and a planar or curved spherical reference surface.

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Continuation-In-Part of PCT/EP01/14314
(Z) 00117 PUS